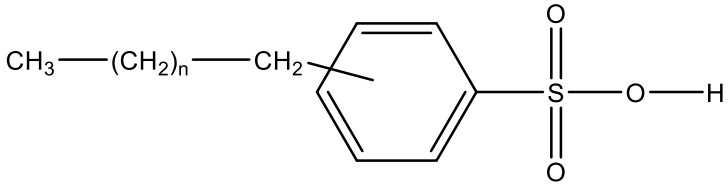
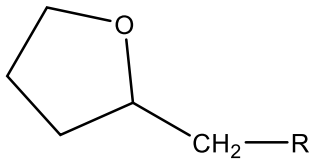
We claim:

1. A composition consisting of an alkylbenzenesulfonic acid having structure (I), wherein n is an integer from 0 to 16;

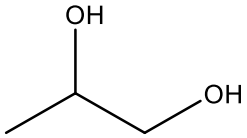


(I); and

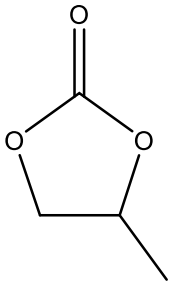
a solvent which is either selected from the group consisting of solvents having structures (II), (wherein R is selected from the group consisting of -(-O-CH_2-CH_2-)$_{n'}$-OH, -OH, and -O-C(=O)-CH_3, wherein n' is equal to 1, 2, 3, or 4), a solvent having structure (III), a solvent having structure (IV), and a solvent having structure (V), or a solvent mixture, of at least two solvents selected from this group;



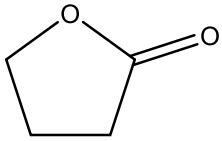
(II),



(III),

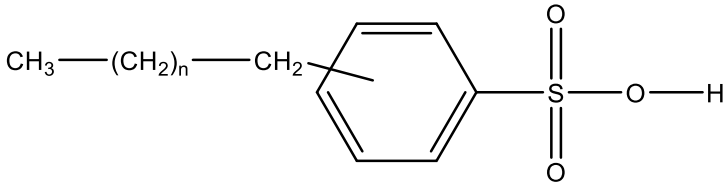


(IV),



(V).

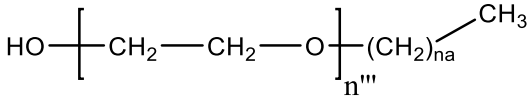
2. A composition consisting of an alkylbenzenesulfonic acid selected having structure (I), wherein n is an integer from 0 to 16;



(I);

a solvent which is either selected from the group consisting of solvents having structures (II), (wherein R is selected from the group consisting of -(-O-CH_2-CH_2-)$_{n'}$-OH, -OH, -O-C(=O)-CH_3, wherein n' is equal to 1, 2, 3, or 4), a solvent having structure (III), a solvent having structure (IV), and a solvent having structure (V), or a solvent mixture, of at least two solvents selected from this group; and a surfactant.

3. The composition of claim 2, wherein the surfactant is a polymeric surfactant having structure (VI), wherein n''' is the number of polymer repeat unit and na is the number of CH_2 spacer moieties, wherein na is an integer from 8 to 14;

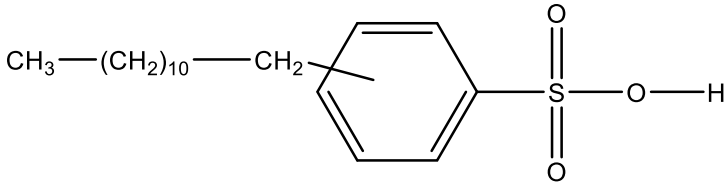


(VI).

4. The composition of claim 2, wherein for said alkylbenzenesulfonic acid n is an integer from 8 to 16.

5. The composition of claim 2, wherein for said alkylbenzenesulfonic acid n is an integer from 8 to 10.

6. The composition of claim 2, wherein for said alkylbenzenesulfonic acid it has structure (Ia)

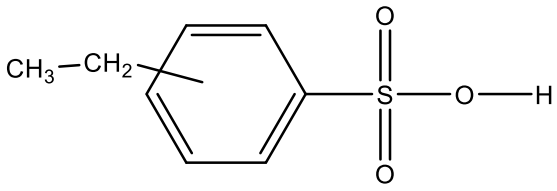


(Ia).

7. The composition of claim 2, wherein for said alkylbenzenesulfonic acid n is an integer from 0 to 10.

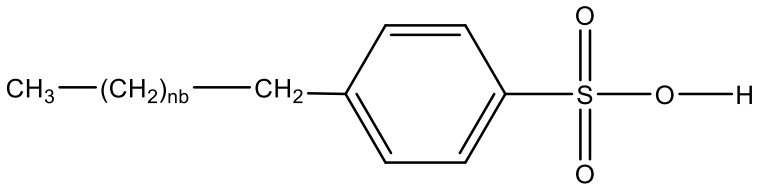
8. The composition of claim 2, wherein for said alkylbenzenesulfonic acid n is an integer from 0 to 2.

9. The composition of claim 2, wherein for said alkylbenzenesulfonic acid has structure (Ib);



(Ib).

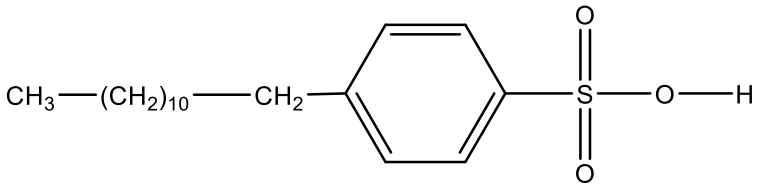
10. The composition of claim 2, wherein said alkylbenzensulfonic acid has structure (Ic), wherein nb is an integer from 0 to 16;



(Ic).

11. The composition of claim 10, wherein nb is an integer from 8 to 10.

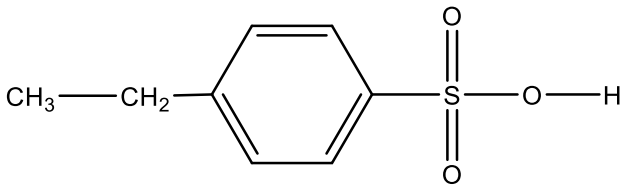
12. The composition of claim 10, wherein said alkylbenzenesulfonic acid has structure (Id);



(Id).

13. The composition of claim 10, wherein nb is an integer from 0 to 5.

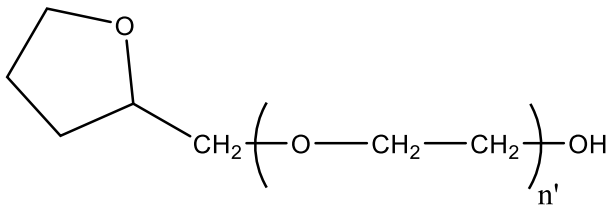
14. The composition of claim 10, wherein said alkylbenzenesulfonic acid has structure (Ie);



(Ie).

15. The composition of claim 2, wherein said solvent is a single solvent which has a structure falling within the scope of structures (II).

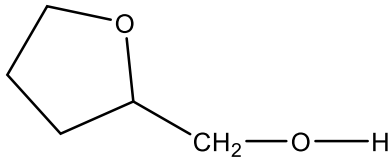
16. The composition of claim 2, wherein said solvent has structure (IIa), wherein n' is 1, 2, 3 or 4;



(IIa).

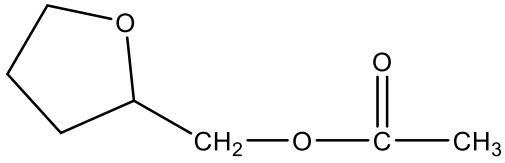
17. The composition of claim 16, wherein said solvent is a mixture of at least two solvents having structure (IIa) having different values of n' 1, 2, 3, or 4.

18. The composition of claim 2, wherein said solvent has structure (IIf);



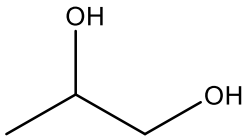
(IIf).

19. The composition of claim 2, wherein said solvent has structure (IIg);



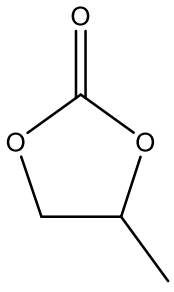
(IIg).

20. The composition of claim 2, wherein said solvent has structure (III);



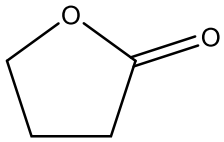
(III).

21. The composition of claim 2, wherein said solvent has structure (IV);



(IV).

22. The composition of claim 2, wherein said solvent has structure (V);



(V).

23. A process comprising the steps;

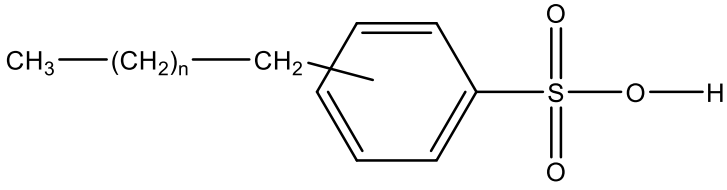
i) heating the composition of claim 2, at a temperature which is from about room temperature to about 100°C;

ii) dipping a substrate coated with a patterned photoresist film into said heated composition for a time from about 1 minutes to about 60 minutes, until a dipped substrate with a removed photoresist film, results;

iii) after dipping step ii), rinsing said dipped substrate with a removed photoresist film with either isopropyl alcohol, water or a mixture of isopropyl alcohol and water to remove any residual composition from dipping step ii), producing a clean substrate;

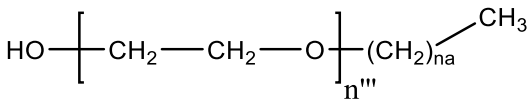
iv) drying said clean substrate, by either spin drying it in air, or by using a stream of nitrogen or air to dry it.

24 A composition consisting essentially of an alkylbenzenesulfonic acid selected having structure (I), wherein n is an integer from 0 to 16;



(I); and

a solvent which is either selected from the group consisting of solvents having structures (II), (wherein R is selected from the group consisting of -(-O-CH_2-CH_2-)$_{n'}$-OH, -OH, and -O-C(=O)-CH_3, wherein n' is equal to 1, 2, 3, or 4), a solvent having structure (III), a solvent having structure (IV), and a solvent having structure (V), or a solvent mixture, of at least two solvents selected from this group; and a surfactant and further wherein said surfactant is a polymeric surfactant having structure (VIII), wherein n''' is the number of polymer repeat unit and na is the number of CH_2 spacer moieties, wherein na is an integer from 8 to 14;



(VI).